

IN THE CLAIMS:

Please CANCEL claims 49-54 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 43-46 and 48, as follows. For the Examiner's convenience, all the claims currently pending in this application, including those not currently being amended, have been reproduced below.

1-42. (Cancelled)

43. (Currently Amended) A scanning exposure apparatus for exposing a substrate to a pattern, said apparatus comprising:

an exposure system which exposes the substrate to the pattern with respect to a unit region, to which the pattern is transferred, of the substrate;

a determination system which determines whether a condition of an exposure performed by said exposure system is allowable during the exposure; ~~and~~

a control system which causes said exposure system to continue exposing a remaining region in the unit region of the substrate to the pattern, even after said determination system makes a negative determination for the unit region; and

a user interface which informs the apparatus of the unit region, for which said determination system makes a negative determination, of the substrate.

44. (Currently Amended) An apparatus according to claim 43, wherein the condition of the exposure ~~includes~~ concerns a position of a region of the substrate.

45. (Currently Amended) An apparatus according to claim 44, further comprising an optical system for projecting the pattern to the substrate, wherein the position is a position in a direction ~~along which the pattern is projected~~ parallel to the optical axis of the optical system.

46. (Currently Amended) An apparatus according to claim 43, wherein the condition of the exposure ~~includes~~ concerns a precision of an exposure control performed by said exposure system.

47. (Previously Presented) An apparatus according to claim 46, wherein the precision of the exposure control includes at least one of an alignment sync control precision and an exposure amount control precision.

48. (Currently Amended) A device manufacturing method comprising steps of:
~~a step of~~ exposing a substrate to a pattern using an exposure apparatus as defined
in claim 43; and
developing the exposed substrate.

49-54. (Cancelled)